CHEMISTRY OF MATERIALS

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# Editorial

## *Chemistry of Materials*—20 Years On and On the Rise

In 2008, *Chemistry of Materials* will enter its 20th year, and by most measures, it will be a significant milestone. The journal was first published in 1989, with three editorial offices in North America publishing 128 papers. In 2008, we will have 12 editorial offices, based in five different countries, publishing close to 1000 papers. During the same period, the journal's publishing frequency has also increased from 6 to 26 issues per year.

Statistically, 2007 was one of the journal's best years on record. According to Thomson Scientific, citations for 2006 increased by 16% to 38,890 compared to citations for the previous year (Figure 1). This ranked *Chemistry of Materials* ***as first for citations in the materials science category*** and fourth in the physical chemistry category. The journal's ***impact factor of 5.104*** for 2006 was also the highest on record, surpassing 5.0 for the first time. Additionally, following the trend of previous years, the projected number of submitted manuscripts is expected to increase by about 20% over the number submitted in 2006. Despite this impressive growth in the number of submissions, rapid publication times have been maintained, with an average time of 35 days from receipt to decision.

The growth in submissions is naturally linked with a number of practical challenges. To deal with the increased manuscript load, in January 2008, a new Editor, Jean-Luc Bredas (Georgia Institute of Technology), will be added. Prof. Bredas brings to the journal diverse and needed expertise in computational materials chemistry, conducting polymers, organic semiconductors, and organic optics. He will be a most welcome addition to *Chemistry of Materials* and will be the fifth new Editor since January 2005. Six new members will also be joining the Editorial Advisory Board, serving three year terms from 2008 to 2010: Mietek Jaroniec (Kent State University); Ram Seshadri (University of California, Santa Barbara); Claudia Wickleder (University of Siegen); Orlin Velev (North Carolina State University); Stanislaus Wong (State University of New York, Stony Brook); and Lynn Loo (Princeton University). Their contributions to the journal will be greatly appreciated.

The increased manuscript load inevitably also leads to a widening gap between submissions and publications. The growing number of submissions means that editorial staff must conduct a preliminary review of all submitted manuscripts and only send out for review those that are most likely to be published. We ask that authors are considerate of the fact that submitted manuscripts are carefully examined by experts in the editorial offices prior to a decision being made regarding their suitability for publication in *Chemistry of Materials*. Central to consideration for sending manuscripts for external peer review is whether manuscripts provide a "significant advance" in a given area of materials chemistry. Therefore, authors are encouraged to carefully follow the instructions for preparing and submitting manuscripts and to ensure that a statement on "significant advance" is included and clearly stated in the submission package. Manuscripts not containing this statement are likely to be considered incomplete by the Editors and may result in the manuscript being rejected without external review. This policy was introduced in 2003 and is a valuable screening tool to ensure that *Chemistry of Materials* continues to publish cutting-edge research and the latest breakthroughs in all fields of materials-related chemistry.

Recent trends in submissions from Asian authors have continued, with China being the second highest source of manuscripts published in the journal after the United States. Authors from Asia made up 23% of all manuscripts published, and these numbers look to increase in coming years. This is clear evidence that *Chemistry of Materials* is a truly international journal. On the back of this, 2007 also saw the first ever meeting of the Editorial Advisory Board outside of the United States,

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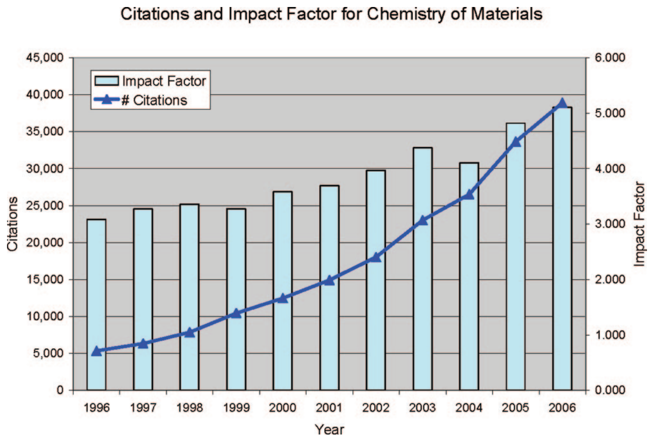

**Figure 1.** Impact factor and citation data. Source: Thomson Scientific (ISI) Journal Citation Reports.

held in Shanghai in October. The meeting provided a forum for a number of Editorial Advisory Board members (Rigoberto Advincula, Jin-Ho Choy, Susumu Kitagawa, Li-Jun Wan, and Dongyuan Zhao), Editor-in-Chief Len Interrante, and myself to discuss future directions of the journal. Jack Ochs (Vice President, Strategic Development and Analysis) and James Liu (Assistant Director, Software Engineering) provided an update of the journal, including the newly implemented ACS Paragon Plus system.

The change from ACS Paragon to the new ACS Paragon Plus system occurred in July 2007 after many months of preparations by editorial staff. Thanks to their hard work, the transition went smoothly, and information has been gathered to assist in further development of the system. Feedback is welcomed from authors and reviewers in the next update of the system that is currently in the planning stage, to help ensure faster and more efficient processing of manuscripts.

We bid farewell to two of our editorial staff in 2007. Suzanne Merten served for 10 years in Elsa Reichmanis' office, and Rob Johnson worked for three years in my office. We thank them both for their outstanding contributions—from keeping the offices running smoothly to tirelessly following up on reviews and providing the necessary information and assistance for the rapid handling of manuscripts. We wish them well in their new endeavors. Measures have been put in place in these editorial offices to ensure that manuscripts will be promptly handled during these transition stages.

In early 2008 *Chemistry of Materials* will feature a special issue on "Templated Materials". This issue will contain a number of reviews, as well as articles and communications. On the basis of the impressive success of previous special issues in *Chemistry of Materials*, this promises to be a landmark issue for the journal, in an area of great interest for the materials science community. We thank Ferdi Schüth (Editor) and Mietec Jaroniec (Co-Editor) for their efforts in promoting and coordinating this issue. Suggestions from authors and reviewers for topics for future special issues are always welcome.

The *Chemistry of Materials* 20-year milestone is a reflection of the continued strong support from authors, reviewers, and our readers. We are thankful for the generous contribution of the time and expertise of our reviewers to provide advice to the Editors for accepting or rejecting manuscripts. We also encourage authors to continue to submit their latest, significant developments to *Chemistry of Materials*. The efforts of the Editorial Advisory Board, who assist with adjudicating difficult cases, are also gratefully acknowledged.

We are looking forward to a significant and successful 2008, in what promises to be a banner 20th year for *Chemistry of Materials*.

**Frank Caruso**

*Editor*

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